

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

|             |                                                                                                                     |             |                      |
|-------------|---------------------------------------------------------------------------------------------------------------------|-------------|----------------------|
| Applicant:  | Gabrie et al.                                                                                                       | Docket No.: | INF 2006 VJ 33543 US |
| Serial No.: | 10/586,788                                                                                                          | Art Unit:   | 2893                 |
| Filed:      | September 2, 2008                                                                                                   | Examiner:   | Yushin, Nikolay K.   |
| For:        | Plasma Excited Chemical Vapor Deposition Method<br>Silicon/Oxygen/Nitrogen-Containing-Material and Layered Assembly |             |                      |

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**AMENDMENT ACCOMPANYING RCE**

Dear Sir:

Applicant respectfully submits the following amendments and remarks in conjunction with a Request for Continued Examination and in response to the final Office Action dated November 4, 2009 and Advisory Action dated January 25, 2010. Applicant respectfully requests that the amendments and remarks presented herein be entered, and respectfully requests reconsideration of the claims.